

Tao Zhang

List of Publications by Year in descending order

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20
papers

363
citations

759233

12
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794594

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all docs

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docs citations

20
times ranked

328
citing authors

#	ARTICLE	IF	CITATIONS
1	Investigation on the interface trap characteristics in a p-channel GaN MOSFET through temperature-dependent subthreshold slope analysis. <i>Journal Physics D: Applied Physics</i> , 2022, 55, 095112.	2.8	9
2	GaN High-Electron-Mobility-Transistor on Free-Standing GaN Substrate With Low Contact Resistance and State-of-the-Art $I_{\text{ON}}/I_{\text{OFF}}$ Value. <i>IEEE Transactions on Electron Devices</i> , 2022, 69, 968-972.	3.0	7
3	High-Performance E-Mode p -Channel GaN FinFET on Silicon Substrate With High $I_{\text{ON}}/I_{\text{OFF}}$ and High Threshold Voltage. <i>IEEE Electron Device Letters</i> , 2022, 43, 705-708.	3.9	16
4	Current transport mechanism of AlGaIn-channel Schottky barrier diode with extremely low leakage current and high blocking voltage of 2.55 kV. <i>Applied Physics Letters</i> , 2022, 120, 092102.	3.3	1
5	Mechanism of low Ohmic contact resistance to p-type GaN by suppressed edge dislocations. <i>Applied Physics Letters</i> , 2022, 120, .	3.3	8
6	Mechanism of current-collapse free for lateral GaN Schottky barrier diodes utilizing polarization-induced hole injection. <i>Applied Physics Letters</i> , 2022, 120, 232101.	3.3	1
7	Current Transport Mechanism of High-Performance Novel GaN MIS Diode. <i>IEEE Electron Device Letters</i> , 2021, 42, 304-307.	3.9	12
8	Investigation of an AlGaIn-channel Schottky barrier diode on a silicon substrate with a molybdenum anode. <i>Semiconductor Science and Technology</i> , 2021, 36, 044003.	2.0	4
9	Current-Collapse Suppression of High-Performance Lateral AlGaIn/GaN Schottky Barrier Diodes by a Thick GaN Cap Layer. <i>IEEE Electron Device Letters</i> , 2021, 42, 477-480.	3.9	18
10	Comprehensive Annealing Effects on AlGaIn/GaN Schottky Barrier Diodes With Different Work-Function Metals. <i>IEEE Transactions on Electron Devices</i> , 2021, 68, 2661-2666.	3.0	15
11	A 0.43 V/90 nA/mm Lateral AlGaIn/GaN Schottky Barrier Diode With Plasma-Free Groove Anode Technique. <i>IEEE Electron Device Letters</i> , 2021, 42, 1747-1750.	3.9	4
12	Lateral GaN Schottky Barrier Diode for Wireless High-Power Transfer Application With High RF/DC Conversion Efficiency: From Circuit Construction and Device Technologies to System Demonstration. <i>IEEE Transactions on Industrial Electronics</i> , 2020, 67, 6597-6606.	7.9	32
13	A 5.8-GHz High-Power and High-Efficiency Rectifier Circuit With Lateral GaN Schottky Diode for Wireless Power Transfer. <i>IEEE Transactions on Power Electronics</i> , 2020, 35, 2247-2252.	7.9	60
14	Leakage current mechanisms of groove-type tungsten-anode GaN SBDs with ultra low turn-ON voltage and low reverse current. <i>Solid-State Electronics</i> , 2020, 169, 107807.	1.4	15
15	A > 3 kV/ 2.94 m^2 and Low Leakage Current With Low Turn-On Voltage Lateral GaN Schottky Barrier Diode on Silicon Substrate With Anode Engineering Technique. <i>IEEE Electron Device Letters</i> , 2019, 40, 1583-1586.	3.9	50
16	High-performance lateral GaN Schottky barrier diode on silicon substrate with low turn-on voltage of 0.31 V, high breakdown voltage of 2.65 kV and high-power figure-of-merit of 2.65 GW cm^2 . <i>Applied Physics Express</i> , 2019, 12, 046502.	2.4	27
17	AlGaIn-Channel Gate Injection Transistor on Silicon Substrate With Adjustable $4\text{--}7$ -V Threshold Voltage and 1.3-kV Breakdown Voltage. <i>IEEE Electron Device Letters</i> , 2018, 39, 1026-1029.	3.9	21
18	InGaIn-channel high-electron-mobility transistor with enhanced linearity and high-temperature performance. <i>Applied Physics Express</i> , 2018, 11, 094101.	2.4	13

#	ARTICLE	IF	CITATIONS
19	A 1.9 kV/2.61 mA, 10^4 cm ² Lateral GaN Schottky Barrier Diode on Silicon Substrate with Tungsten Anode and Low Turn-On Voltage of 0.35 V. IEEE Electron Device Letters, 2018, , 1-1.	3.9	23
20	Trap state analysis in AlGaIn/GaN/AlGaIn double heterostructure high electron mobility transistors at high temperatures. Applied Physics Letters, 2017, 110, 252102.	3.3	27